



IIT ROORKEE



NPTEL ONLINE  
CERTIFICATION COURSE

# CMOS DIGITAL VLSI DESIGN

## MOS TRANSISTOR BASICS - I

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# Outline

- MOSFET as a Switch
- MOSFET Structure
- Types of MOSFET
- Threshold Voltage of MOSFET
- Current-Voltage Characteristics
- Transfer Characteristics and Sub-threshold Slope
- Basic Equations (to be remembered)
- Recapitulation

# MOSFET as a Switch

- Metal Oxide Semiconductor Field Effect Transistors (MOSFETs) can be considered as a switch which operates with proper biasing.
- This helps to give many answers itself-
  1. **For what value of gate voltage device will turn ON (threshold voltage)?**
  2. What is the resistance between source and drain when device is ON (OFF)?
  3. What limits the speed of the device?

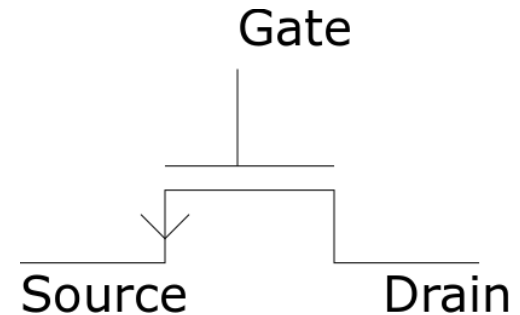
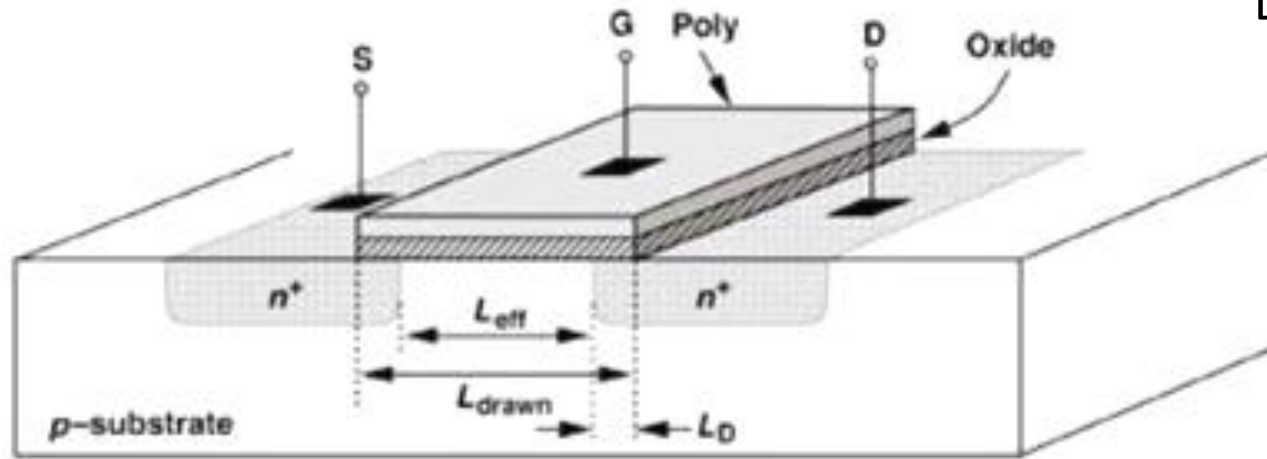


Figure : MOS device Schematic

# MOSFET Structure



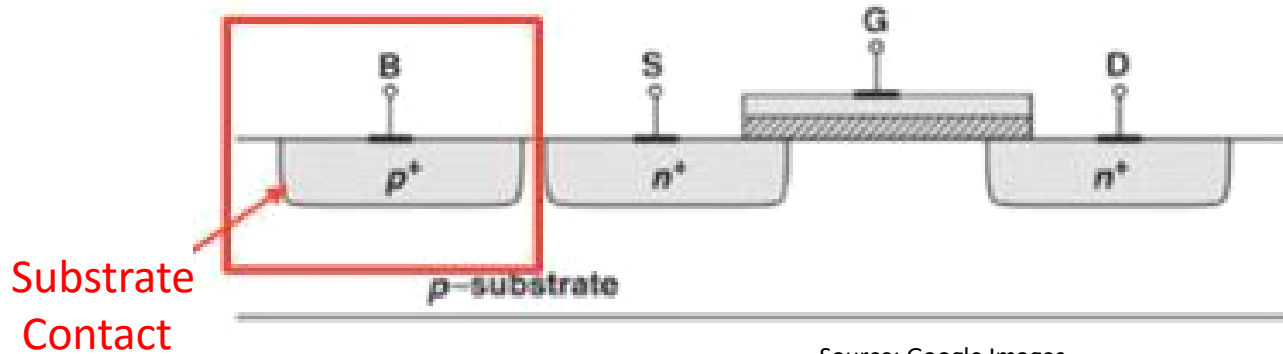
$L_D$ : Side Diffusion Length

$$L_{eff} = L_{drawn} - 2L_D$$

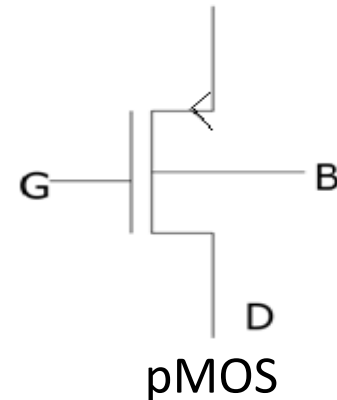
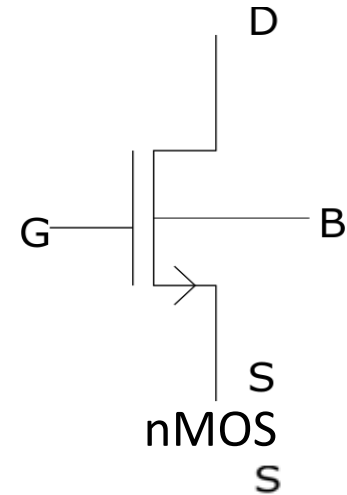
- If MOS structure is symmetric then why one n-region is called source and another is drain?

Source: Google Images

# Body Terminal and MOS symbols



Source: Google Images

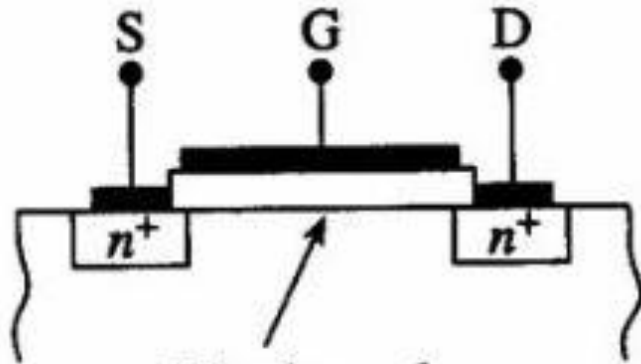


- The substrate bias should be connected with the negative most supply of the system.
- nMOS and pMOS are in general made in same wafer, in which one device can be placed in local substrate called as well.

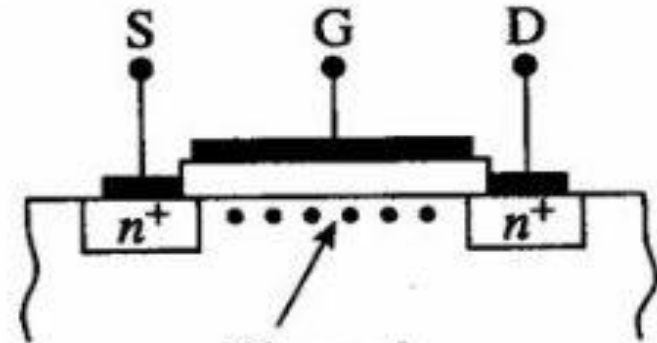




# Types of MOSFET



No channel  
when  $V_G = 0$   
Enhancement MOSFET



Channel  
when  $V_G = 0$   
Depletion MOSFET

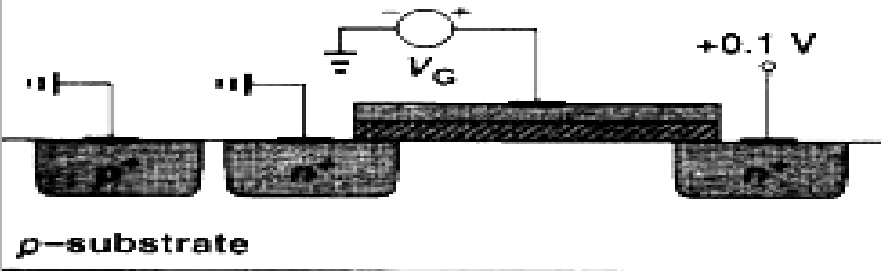
- Throughout the course we will discuss about Enhancement MOSFET.

Source: R. F. Pierret, "Semiconductor Device Fundamentals," Addison Wesley Longman.

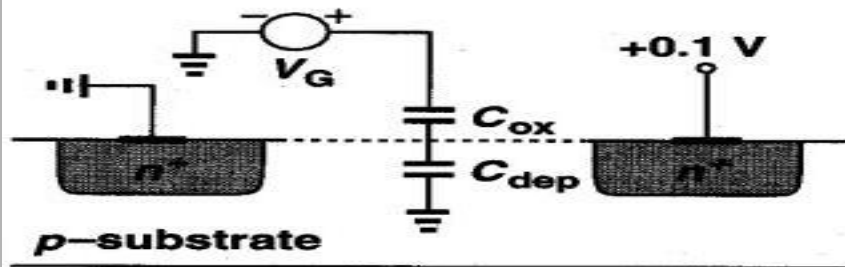


# Threshold Voltage of MOSFET

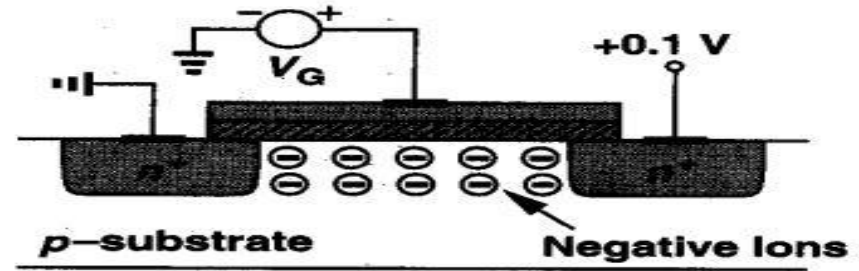
- With keeping constant drain bias, we'll analyze the different modes



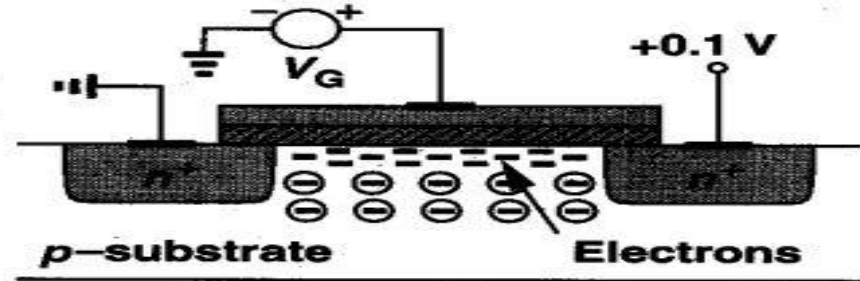
Device under consideration



Onset of Inversion Layer



Formation of Depletion Region



Formation of Inversion Layer

Source: B. Razavi, "Design of Analog CMOS Integrated Circuit," McGraw-Hill Education Pvt. Ltd., 2002.

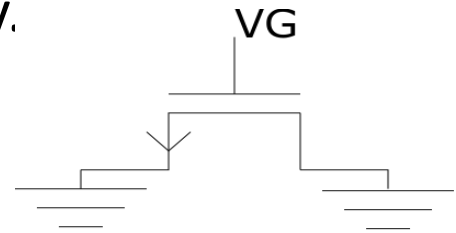
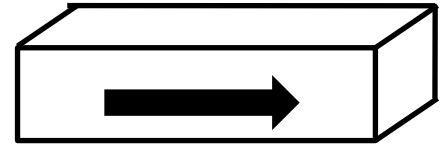
- As the gate and substrate forms a capacitor, the applied  $V_G$  images a opposite charge on the substrate.
  - The increase in  $V_G$  increases the drop across gate-oxide and also the width of depletion region. Therefore, depletion capacitance ( $C_{dep}$ ) and oxide capacitance ( $C_{ox}$ ) are in series.
  - Now, what would be the threshold value?
- The value of minimum gate voltage which inverts the surface, and hence an effective channels gets formed.

$$V_{TH} = \Phi_{MS} + 2\Phi_F + \frac{Q_{dep}}{C_{ox}}$$

where  $\Phi_{MS} = \Phi_M - \Phi_S$  is difference between metal and semiconductor work-functions

# Current-Voltage Characteristics

- To derive I-V characteristics, we make two observations:
  - The current ( $I$ ) flowing in a semiconductor is the product of charge density along the direction of current flow and the velocity of the charge carriers.
$$I = Q \cdot v$$
  - Consider an n-MOSFET whose both source and drain terminals are grounded. Then we need to find the charge density.

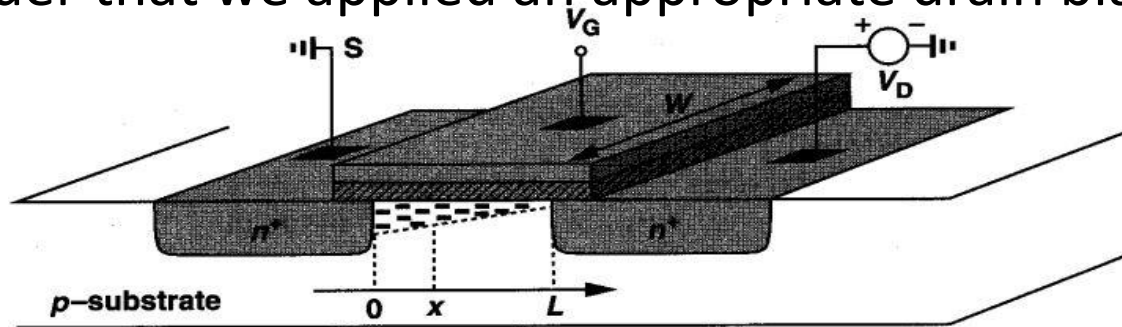


- We assume the ONSET of inversion takes place at  $V_{GS}=V_{TH}$ . So, the inversion charge density is proportional to  $V_{GS}-V_{TH}$ , *i.e.*

$$Q=WC_{OX}(V_{GS}-V_{TH})$$

with  $W$  be the width of the device and  $C_{OX}$  being the gate oxide (per unit area)

- Next, consider that we applied an appropriate drain bias.



Source: B. Razavi, "Design of Analog CMOS Integrated Circuit," McGraw-Hill Education Pvt. Ltd., 2002.

# Assumptions

- Gradual Channel Approximation
- Charge Sheet Model

- As there is a voltage difference occur in the channel. So, at any point  $x$ , the charge density can be defined as-

$$Q(x) = WC_{OX} [V_{GS} - V_{TH} - V(x)]$$

where  $V(x)$  is the channel potential at point  $x$ .

- Therefore, current is given by-

$$I_D = -WC_{OX} [V_{GS} - V_{TH} - V(x)]v$$

where  $v = \mu E = \mu(-dV(x)/dx)$ .  $\mu$  is the mobility of the carrier and for simplicity we use the symbol  $\mu_n$  for electrons, present in the channel.

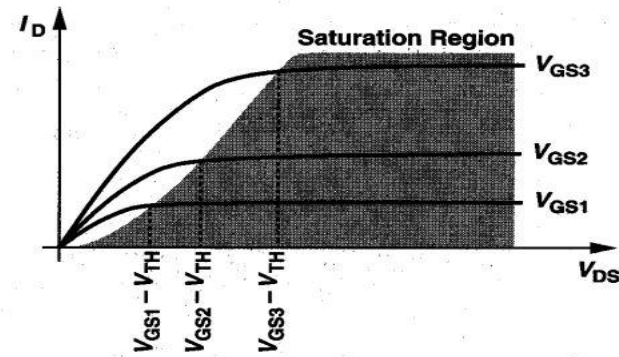
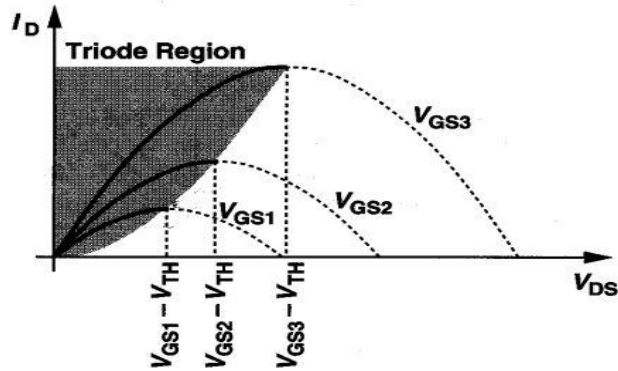
$$I_D = WC_{OX} [V_{GS} - V_{TH} - V(x)] \mu_n \frac{dV(x)}{dx}$$

with applying the proper boundary conditions as  $V(0)=0$  and  $V(L)=V_{DS}$

$$\int_{x=0}^L I_D dx = \int_{V=0}^{V_{DS}} WC_{OX} [V_{GS} - V_{TH} - V(x)] \mu_n dV$$

Since the current is constant throughout the channel region.

$$I_D = \mu_n \frac{W}{L} C_{OX} [(V_{GS} - V_{TH}) V_{DS} - \frac{V_{DS}^2}{2}]$$



The peak value of the parabolas can be calculated by  $\partial I_D / \partial V_{DS}$

We have found that the peak occurs at  $V_{DS} = V_{GS} - V_{TH}$ .

$$I_{D,max} = \mu_n C_{OX} \frac{W}{2L} (V_{GS} - V_{TH})^2$$

Source: B. Razavi, "Design of Analog CMOS Integrated Circuit," McGraw-Hill Education Pvt. Ltd., 2002.

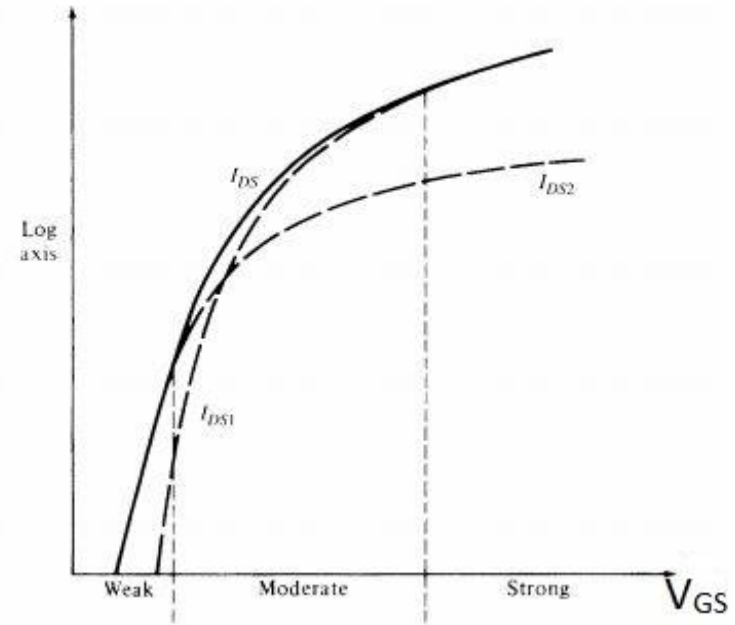




# Transfer Characteristics

- We define the inversion in three parts-
  1. Weak Inversion -  $\Phi_F < \psi_S < 2\Phi_F$
  2. Moderate Inversion -  $\psi_S \approx 2\Phi_F$
  3. Strong Inversion -  $\psi_S = \Delta\Phi + 2\Phi_F$

where  $\psi_S$  is the surface potential,  $\Phi_F$  is the difference between intrinsic level and Fermi level,  $\Delta\Phi \approx 6\Phi_t$  ( $\Phi_t$  is  $kT/q$ ).



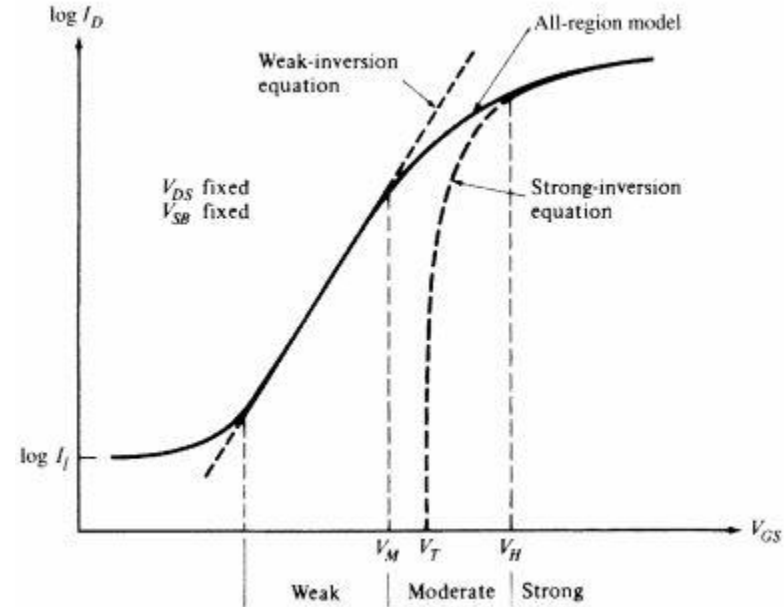
Source: Y. Tsividis and C. McAndrew, "The MOS Transistor," Oxford University Press, 2013.

# Sub-threshold Slope

- The slope of transfer characteristics determines how well a transistor can be turned off by reducing  $V_{GS}$ , for digital applications.

$$S = \frac{dV_{GS}}{d(\log I_D)}$$

- The conventional limit of  $S$  for MOSFET is 60mV/decade.



Source: Y. Tsividis and C. McAndrew, "The MOS Transistor," Oxford University Press, 2013.

## Basic Equations to be remembered

- In Saturation Region, the drain current is given by-

$$I_{D,\max} = \mu_n C_{OX} \frac{W}{2L} (V_{GS} - V_{TH})^2$$

- The Saturation takes place when-  $[V_{GS} - V_{TH}] \leq V_{DS}$

- In linear region-  $I_D = \mu_n \frac{W}{L} C_{OX} [(V_{GS} - V_{TH})V_{DS} - \frac{V_{DS}^2}{2}]$

- If  $V_{DS} \ll 2(V_{GS} - V_{TH})$ , then the ON resistance offered by MOSFET is

$$R_{ON} = 1/\mu_n \frac{W}{L} C_{OX} (V_{GS} - V_{TH})$$

# Recapitulation

- MOS transistor can be used as a **Voltage Controlled Switch (VCS)** as well as **Voltage Variable Resistor (VVR)**
- N-MOS and P-MOS can be fabricated in a single wafer and these are basic blocks of all Digital /Analog circuits.
- In **linear region**, **transistor acts as a resistor** while in **saturation** it acts as a **current source**.
- Steepness of Sub-threshold Slope decides the speed of transitions between its OFF and ON states.

# Thank You

